

Press Release

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Nanonex delivered Advanced Nanoimprint Tool NX-2600 BA to Aarhus University, Denmark

Princeton NJ, April 15, 2011:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of Nanonex's NX-2600 BA system to Aarhus University at Denmark. Nanonex is proud to support the cutting edge research at Aarhus University.

The Nanonex NX-2600 BA is a full wafer nanoimprinter and photolithography aligner. It features all imprint forms: thermal, photo-curable, embossing and photolithography, with sub-5 nm imprinting resolution and sub-1 micron alignment accuracy. Based on the Nanonex unique patented Air Cushion Press™ technology, the NX-2600 offers unsurpassed uniformity regardless of backside topology, wafer or mask flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mask and substrate, which significantly increases mask lifetime. The small thermal mass design allows fast thermal cycling resulting in a fast process cycle.

About Nanonex Corporation

Nanonex is the inventor of NIL, the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary NIL solutions and Air-Cushion Press TM can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of over 50 tools world-wide. Visit www.nanonex.com for additional information.